

IFW



PATENT
30205/37328A

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of: Min Ho Jung, et al.

) I hereby certify that this document
referred to as enclosed herewith is being
deposited with the United States Postal
Service via first class mail, in an envelope
addressed to the Commissioner for
Patents, P.O. Box 1450 Alexandria,
Virginia 22313-1450, on June 1, 2005.

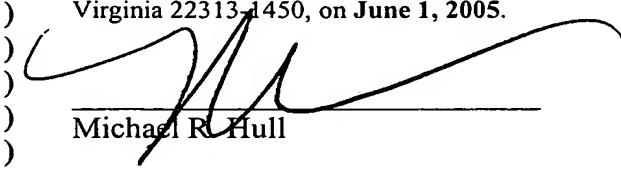
Serial No.: 10/789,055

Filed: February 27, 2004

For: Additive for Photoresist
Composition for Resist Flow Process

Group Art Unit: 1752

Examiner: Sin J. Lee


Michael R. Hull

PRELIMINARY AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Sir:

Please enter the following preliminary amendment in the above-referenced
divisional application.

Amendments to the specification begin on page 2 of this paper.

Amendments to the claims begin on page 3 of this paper.

Remarks begin on page 8 of this paper.